

L Number	Hits	Search Text	DB	Time stamp
1	2	5783938.pn. 6429935.pn.	USPAT	2003/07/16 10:55
-	9364	"chemical mechanical" adj (polishing planarization)	USPAT	2002/07/11 13:29
-	344	("chemical mechanical" adj (polishing planarization)) and (unload\$3 and load\$3)	USPAT	2002/07/01 13:10
-	384	((("chemical mechanical" adj (polishing planarization)) and ("load lock"))	USPAT	2002/07/08 07:55
-	49	((("chemical mechanical" adj (polishing planarization)) and ("load lock"))	USPAT	2002/07/08 07:23
-	2746	("chemical mechanical" adj (polishing planarization)) and CLEAN\$3	USPAT	2002/07/08 07:56
-	251	((("chemical mechanical" adj (polishing planarization)) and CLEAN\$3) AND UNLOAD\$3	USPAT	2002/07/08 07:57
-	3	"9946804"	DERWENT	2002/07/08 12:32
-	9	"9901131"	DERWENT	2002/07/08 12:38
-	4	"0911157"	DERWENT	2002/07/08 12:38
-	1	"10209857"	DERWENT	2002/07/08 12:39
-	9510	"chemical mechanical" adj (polishing planarization)	USPAT	2002/07/11 13:29
-	3276	("chemical mechanical" adj (polishing planarization)) and (wash\$ rins\$ clean\$3)	USPAT	2002/07/11 13:30
-	3235	("chemical mechanical" adj (polishing planarization)) and (wash\$3 rins\$3 clean\$3)	USPAT	2002/07/11 13:30
-	720	((("chemical mechanical" adj (polishing planarization)) and (wash\$3 rins\$3 clean\$3)) and (dress\$3 finish\$3)	USPAT	2002/07/11 13:31
-	245	(((("chemical mechanical" adj (polishing planarization)) and (wash\$3 rins\$3 clean\$3)) and (dress\$3 finish\$3)) and (Cu copper)	USPAT	2002/07/11 13:31
-	71	((((("chemical mechanical" adj (polishing planarization)) and (wash\$3 rins\$3 clean\$3)) and (dress\$3 finish\$3)) and (Cu copper)) and ("oxalic acid" "citric acid" ammonia)	USPAT	2002/07/11 13:32
-	56	(((((("chemical mechanical" adj (polishing planarization)) and (wash\$3 rins\$3 clean\$3)) and (dress\$3 finish\$3)) and (Cu copper)) and ("oxalic acid" "citric acid" ammonia)) and (silica alumina "hydrogen peroxide" "phthalic acid"))	USPAT	2002/07/11 13:33
-	9510	("chemical mechanical" adj (polishing planarization))	USPAT	2002/07/12 15:28
-	2212	((("chemical mechanical" adj (polishing planarization))) and (reaction)	USPAT	2002/07/12 12:44
-	595	((("chemical mechanical" adj (polishing planarization))) and (reaction near10 (metal cu copper))	USPAT	2002/07/12 12:46
-	186	((("chemical mechanical" adj (polishing planarization))) and (reaction near10 (metal cu copper))) and (silica alumina "hydrogen peroxide" "phthalic acid")	USPAT	2002/07/12 13:38
-	0	6007408,6296806,4754089,6126848,5704987,6012966.pn.	USPAT	2002/07/12 13:39
-	6	("6007408" "6296806" "4754089" "6126848" "5704987" "6012966").pn.	USPAT	2002/07/12 13:41
-	6	((("6007408" "6296806" "4754089" "6126848" "5704987" "6012966").pn.) and reaction	USPAT	2002/07/12 13:41
-	22	((("chemical mechanical" adj (polishing planarization))) and (pressuriz\$3 near5 nozzle)	USPAT	2002/07/12 13:43
-	9510	("chemical mechanical" adj (polishing planarization))	USPAT	2002/07/12 15:29
-	50	((("chemical mechanical" adj (polishing planarization))) and ((dress\$3 grind\$3 finish\$3) near5 (lateral\$2 horizontal\$2 slid\$3))	USPAT	2002/07/12 15:30
-	135	156/345.12	USPAT	2003/03/14 13:41

-	1855	(pad cloth) same (condition\$3 same (chemical reaction dissolv\$3))	USPAT	2003/03/17 11:18
-	1855	((pad cloth) same (condition\$3)same (chemical reaction dissolv\$3))	USPAT	2003/03/17 12:07
-	678	((pad cloth) same (condition\$3)same (reaction))	USPAT	2003/03/17 12:08
-	15372	(CMP "chemical mechanical") and (scrap\$3 finish\$3 condition\$3 dress\$3)	USPAT	2003/07/16 08:51
-	3530	(CMP "chemical mechanical") same (scrap\$3 finish\$3 condition\$3 dress\$3)	USPAT	2003/07/16 08:51
-	1922	(CMP "chemical mechanical") with (scrap\$3 finish\$3 condition\$3 dress\$3)	USPAT	2003/07/16 08:49
-	175	156/345.12	USPAT	2003/07/16 08:51
-	0	156/345.12 same (scrap\$3 finish\$3 condition\$3 dress\$3)	USPAT	2003/07/16 08:51
-	130	156/345.12 and (scrap\$3 finish\$3 condition\$3 dress\$3)	USPAT	2003/07/16 08:51